

John H. Weaver Biosketch

John H. Weaver is Professor of Materials Science and Engineering and Professor of Physics at the University of Illinois at Urbana-Champaign. He completed his PhD in solid state physics at Iowa State University/Ames Laboratory USDOE in 1972. He was on the staff of the Synchrotron Radiation Center at the University of Wisconsin-Madison until 1982 when he moved to the University of Minnesota as head of the electronic materials group and where he also served as director of graduate studies for materials science from 1983-1992 and 1997-2000. He moved to the University of Illinois in 2000 where he was head of the MatSE Department until 2003. He was named D.B. Willett Professor of Engineering in the College of Engineering in 2003.

Weaver's research activities focus on the physics and chemistry of surfaces, interfaces, and nanostructures, including fullerenes. He is author of ~490 refereed papers, including 21 chapters and monographs on valence state photoemission, metal/semiconductor interfaces, high temperature superconductors, fullerenes, and semiconductor etching and feature articles in *Scientific American*, *Physics Today*, and *Science*. His Hirsch citation index is 63.

Weaver is a Fellow of the American Physical Society, the American Vacuum Society, and the American Association for the Advancement of Science. He held the 1994-95 Amundson Professorship and received an Alexander von Humboldt Senior Distinguished U.S. Scientist Award to work at the Fritz-Haber-Institut in Berlin. He was University Professor at Tohoku University (Institute for Materials Research) in 1994. He was awarded the Royal Society Kan Tong Po Professorship at the University of Hong Kong in 1995. *Research & Development Magazine* recognized him as their Scientist of the Year in 1997, and Iowa State University recognized him with its Distinguished Achievement Citation in 1998. In 1999, he served as Chief Judge for Singapore's National Science Talent Search, and he received the Medard W. Welch Award of the American Vacuum Society ["for his seminal contributions to the atomic-level understanding of thin-film growth, interfacial interactions, and etching"]. He was the Peter Winchell lecturer at Purdue University in 2000 and the Distinguished Kodak lecturer at Rensselaer Polytechnic Institute in 2003.

Within the AVS, Weaver has served on the executive committees for EMPD and Surface Science [program chair 1988 and division chair 1989], and was Program Chair for the National Symposium (1992). He was elected to the AVS Board of Directors (1990-91) and the presidency (1994-96). He is a member of the Long Range Planning Committee. He was elected vice chair of the Nanoscale Science and Technology Division [division chair 1999 and program chair 2000]. He was chair of the Sixth International Conference on Nanoscale Science and Technology (2000). He served on the Governing Board of the American Institute of Physics (1996-1999) [Executive Committee 1997]. He was elected vice chair (1995-98) and co-chair (1998-2001) of the Surface Science Division of the International Union for Vacuum Science, Techniques, and Applications. He has served as AVS councilor and alternate councilor to IVUSTA (2001-07). He was elected to serve as AVS Trustee for 2002-2004 (chair 2004).

Within the Materials Research Society, Weaver has organized several symposia and chaired the MRS Medal Award subcommittee for several years. He has been on the editorial board of the *Journal of Materials Research*, and he was a principal editor of that journal. Within the American Physical Society, he organized the special postdeadline session on fullerenes in 1991. He has served on numerous program committees for international conferences and review panels for universities and government agencies. He has been a judge for awards that include the R&D IR 100 awards and the COMSATS-IIT Medals for Innovation. He is currently on the International Advisory Boards of the National Center for Physics and the Ghulam Ishaq Khan Institute in Pakistan.

Editorial board appointments have included the *Journal of Vacuum Science and Technology*, *Surface Science*, *Surface Science Reports*, *Surface Review & Letters*, *Journal of Materials Research*, *Chemistry of Materials*, *Journal of Electron Spectroscopy and Related Phenomena*, *Fullerene Science & Technology*, *Chemistry and Physics of Surfaces & Interfaces*, the Royal Society of Chemistry's *Electronic Journal PhysChemComm*, and the *Central European Journal of Physics*. He was a principal editor of the *Journal of Materials Research* and an associate editor for *Surface Science Spectra* and for *Nanostructured Materials*. He was Launch Editor of *JVST Online*.